

Tunable Silicon Fabry-Perot microcavity

C. Angulo Barrios, V.R. Almeida, R.R. Panepucci, B.S. Schmidt and M. Lipson

*School of Electrical and Computer Engineering, Cornell University, Ithaca NY 14853
cb265@cornell.edu*

Abstract: We demonstrate a 20- μm -long tunable optical Fabry-Perot resonator integrated on a silicon-on-insulator waveguide. The device is electrically driven and shows a modulation depth as high as 53% for a power consumption of only 20 mW.

© 2004 Optical Society of America

OCIS codes: (230.3120) Integrated optics devices; (230.5750) Resonators; (250.5750) Waveguide modulators

1. Introduction

Silicon-based optical tunable devices are key components for the realization of CMOS compatible optoelectronic circuits. Since crystalline Si does not have linear electro-optic effect, its refractive index is varied through either thermo-optic effect or free-carrier effect. Typical refractive index changes created by these methods are small (on the order of 10^{-3}) and therefore Si tunable planar devices demonstrated so far [1-4] require long interaction lengths and high power consumption.

High finesse microcavities are ideal for achieving tunability in a short length since their transmission is highly sensitive to small index changes in the cavity [5]. In this paper, we report on the fabrication and characterization of a 20- μm -long tunable F-P cavity on silicon-on-insulator (SOI).

2. Device structure and fabrication

Fig. 1 shows a schematic of the device [5]. It consists of a planar F-P cavity formed by two distributed Bragg reflectors (DBR) in an undoped SOI rib waveguide. Both DBRs consist of three Si/SiO₂ periods etched down to the buried oxide (BOX) layer. p⁺ and n⁺ areas are defined in the cavity region at each side of the rib, defining a p-i-n diode. The p-i-n diode is laterally limited by isolation trenches down to the BOX layer. SiO₂ covers the whole structure. Fig. 2 shows a scanning electron microscope photograph of the planar F-P microcavity.

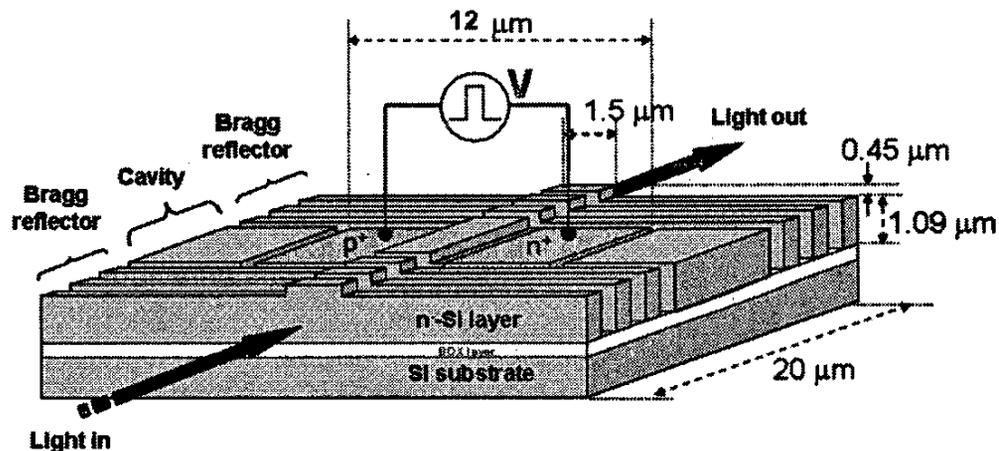


Fig. 1. Schematic of a tunable Si F-P microcavity. A lateral p-i-n diode is used to drive current into the cavity region.

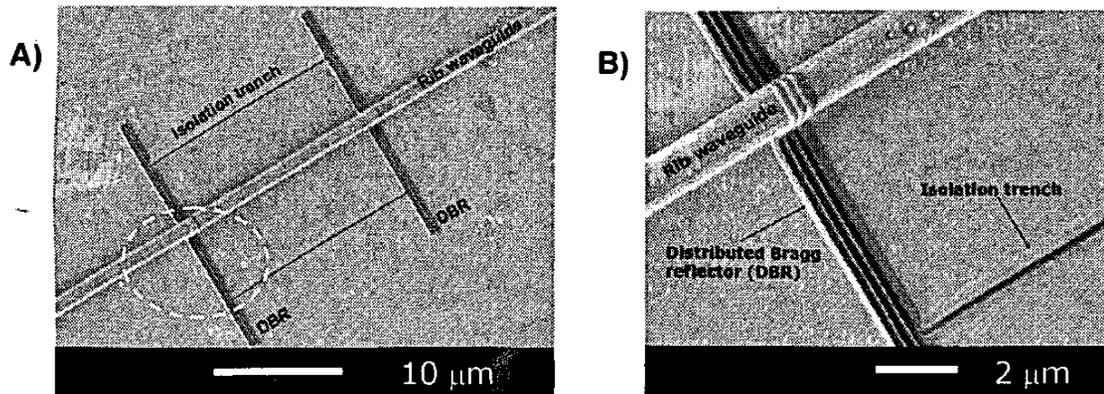


Fig. 2. A) Top view SEM photograph of a planar F-P microcavity integrated on a SOI ridge waveguide. B) Enlargement of the dotted region in A).

3. Results and discussion

Fig. 3 shows the transmission spectrum of the fabricated microcavity over the 1520-1600 nm wavelength range. The full width at half maximum of the resonance peak at 1.553 μm is 1.54 nm. This represents a finesse of 11.2. To our knowledge, this is the highest finesse reported for a planar F-P waveguide microcavity in Si.

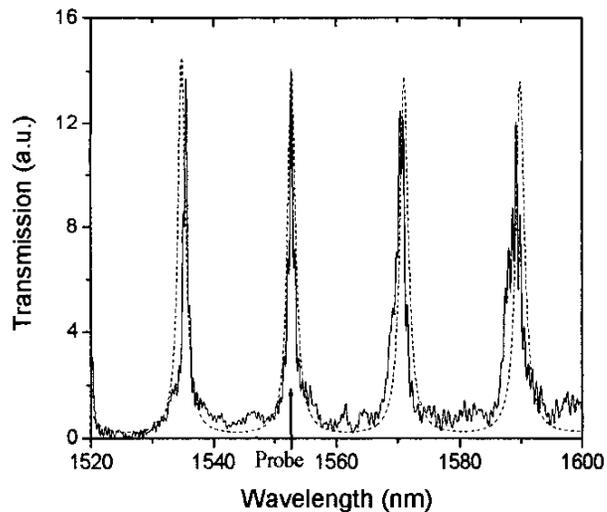


Fig. 3. Experimental (solid line) and calculated [5] (dashed line) transmittivity spectra of the F-P microcavity for the fundamental TE-like mode in the 1520-1600 nm wavelength range.

Fig. 4 shows the measured modulation depth (M) of the device at 1552.89 nm as a function of the dissipated power (P_d). M is defined as $(P_{\text{OFF}} - P_{\text{ON}})/P_{\text{OFF}}$, where P_{OFF} and P_{ON} are the transmitted optical powers in the OFF and ON states, respectively. A maximum M of 53% is obtained at $P_d = 20$ mW. This dissipated power is two orders of magnitude smaller than that reported for longer F-P cavity devices [3,4].

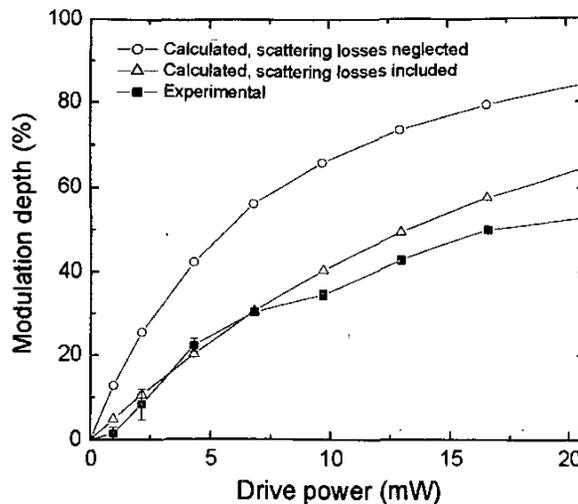


Fig. 4. Experimental (square dots) and calculated (triangular dots) modulation depth of the studied device at 1552.89 nm as a function of the dissipated power. The calculated modulation depth of a similar device with negligible scattering losses is shown in circular dots.

The dependence of the change in index with temperature, $\Delta n_{\text{eff}}/\Delta T$, provides an indication of the relative contributions of the free-carrier effect and the thermal effect to the signal modulation. We estimated $\Delta n_{\text{eff}}/\Delta T = +8.7 \times 10^{-5} \text{ K}^{-1}$, revealing a dominating thermal modulation mechanism. However, the obtained $\Delta n_{\text{eff}}/\Delta T$ is significantly smaller than the reported thermo-optic coefficient of Si, $+1.86 \times 10^{-4} \text{ K}^{-1}$ [3], suggesting the existence of free-carrier dispersion which opposes the thermo-optic effect.

4. Conclusion

We demonstrate a 20- μm -long electrically-driven tunable F-P microcavity on Si. The high finesse of the cavity increases the sensitivity of the device to small index changes and enables high modulation at low power consumption.

5. References

1. G.V. Treyz, "Silicon Mach-Zehnder waveguide interferometers operating at 1.3 μm ," *Electronics Lett.* 27(2), pp. 118-120, 1991.
2. C.Z. Zhao, E.K. Liu, G.Z. Li, Y. Gao, and C.S. Guo, "Zero-gap directional coupler switch integrated into a silicon-on-insulator for 1.3- μm operation," *Optics Lett.*, vol.21, no.20, p.1664, 1996.
3. G. Cocorullo, M. Iodice and I. Rendina, "All-silicon Fabry-Perot modulator based on the thermo-optic effect," *Optics Lett.*, vol. 19, no.6, p.420-422, 1994.
4. C. Cocorullo, M. Iodice, I. Rendina, and P.M. Sarro, "Silicon thermo-optical micro-modulator with 700 kHz -3dB bandwidth," *IEEE Photo. Technol. Lett.*, vol. 7, pp. 363-365, 1995.
5. C. Angulo Barrios, V.R. Almeida, and M. Lipson "Low-power-consumption short-length and high-modulation-depth silicon electro-optic modulator," *J. Lightwave Technol.* vol.21, no.4, pp. 1089-1098, 2003.